

WEST[Help](#)[Logout](#)[Interrupt](#)[Main Menu](#)[Search Form](#)[Posting Counts](#)[Show S Numbers](#)[Edit S Numbers](#)[Preferences](#)**Search Results -**

Term	Documents
11369355	0
11369355S	0
"11369355".JPAB,EPAB,DWPI,TDBD.	0

Database:

US Patents Full-Text Database
US Pre-Grant Publication Full-Text Database
JPO Abstracts Database
EPO Abstracts Database
Derwent World Patents Index
IBM Technical Disclosure Bulletins

Refine Search:

(sputtering with temperature with (rate
near3 deposit\$3) with (experiment\$5 or
optimiz\$5 or determin\$3 or depend\$4))

[Clear](#)**Search History****Today's Date: 1/30/2002**

<u>DB Name</u>	<u>Query</u>	<u>Hit Count</u>	<u>Set Name</u>
JPAB,EPAB,DWPI,TDBD	11369355	0	L21
JPAB,EPAB,DWPI,TDBD	369355	2	L20
JPAB,EPAB,DWPI,TDBD	00383072	0	L19
JPAB,EPAB,DWPI,TDBD	383072	1	L18
JPAB,EPAB,DWPI,TDBD	2000383072	0	L17
USPT,PGPB	L14 and L1	0	L16
USPT,PGPB	L13 and L1	0	L15
USPT,PGPB	(Mitsui Chemicals).as.	377	L14
USPT,PGPB	(Nippon Sheet Glass).as.	458	L13
USPT,PGPB	6104530.pn. or 5804102.pn.	2	L12
USPT,PGPB	L7 not L8	31	L11
USPT,PGPB	L9 and ((PDP or (plasma display)) near3 filter) and (silver or Ag)	31	L10
USPT,PGPB	L7 not L8	31	L9
USPT,PGPB	L6 and (silver or Ag)	16	L8
USPT,PGPB	L5 and (silver or Ag)	47	L7
USPT,PGPB	L4 and L5	22	L6
USPT,PGPB	((PDP or (plasma display)) near3 filter)	84	L5
USPT,PGPB	((427/64).icls. or (427/68).icls. or (427/69).icls. or (427/70).icls. or (427/108).icls. or (427/109).icls. or (427/124).icls. or (427/164).icls. or (427/250).icls. or (427/251).icls. or (427/255.32).icls. or (427/255.7).icls. or (204/192.1).icls. or (204/192.14).icls. or (204/192.15).icls. or (204/192.26).icls. or (313/112).icls. or (313/484).icls. or ((313/489)!.ICLS.))	4984	L4
USPT,PGPB	L1 and ((PDP or (plasma display)) near3 filter)	3	L3
USPT,PGPB	6333592.pn. or 6252703.pn. or 6235398.pn.	3	L2
USPT,PGPB	(Nitto Denko).as.	401	L1

WEST[Help](#)[Logout](#)[Interrupt](#)[Main Menu](#)[Search Form](#)[Posting Counts](#)[Show S Numbers](#)[Edit S Numbers](#)[Preferences](#)**Search Results -**

Term	Documents
TEMPERATURE.DWPI,TDBD,EPAB,JPAB.	1056668
TEMP.DWPI,TDBD,EPAB,JPAB.	708670
TEMPS.DWPI,TDBD,EPAB,JPAB.	78763
TEMPERATURES.DWPI,TDBD,EPAB,JPAB.	95284
CELCIUS.DWPI,TDBD,EPAB,JPAB.	199
CELCIU	0
KELVIN.DWPI,TDBD,EPAB,JPAB.	1261
KELVINS.DWPI,TDBD,EPAB,JPAB.	22
DEPOSIT\$3	0
DEPOSIT.DWPI,TDBD,EPAB,JPAB.	118614
(L10 AND (TEMPERATURE OR CELCIUS OR KELVIN OR (DEPOSIT\$3 NEAR3 RATE))) .JPAB,EPAB,DWPI,TDBD.	25

[There are more results than shown above. Click here to view the entire set.](#)

Database:

US Patents Full-Text Database	▲
US Pre-Grant Publication Full-Text Database	
JPO Abstracts Database	
EPO Abstracts Database	
Derwent World Patents Index	
IBM Technical Disclosure Bulletins	▼

Refine Search:

L10 and (temperature or celcius or
kelvin or (deposit\$3 near3 rate))[Clear](#)**Search History****Today's Date: 1/30/2002**

<u>DB Name</u>	<u>Query</u>	<u>Hit Count</u>	<u>Set Name</u>
JPAB,EPAB,DWPI,TDBD	L10 and (temperature or celcius or kelvin or (deposit\$3 near3 rate))	25	L11
JPAB,EPAB,DWPI,TDBD	(sputter\$3 or (vacuum near3 deposit\$3) or \$2CVD or (vapor deposit\$3)) and ((silver or Ag) and (dielectric or oxide or (refractive index))) and (multilayer or (multi layer) or (multiple layer) or ((3 or three or 4 or four or five or 5 or 6 or six or seven or 7 or eight or 8 or nine or 9) layer)))	150	L10
USPT,PGPB	L8 and ((sputter\$3 or deposit\$3) with (temperature or (deposit\$3 near3 rate)))	89	L9
USPT,PGPB	L7 and ((427/\$).icls. or (204/\$).icls. or (313/\$)!.icls.)	171	L8
USPT,PGPB	(sputter\$3 or (vacuum near3 deposit\$3) or \$2CVD or (vapor deposit\$3)) and ((silver or Ag) same (dielectric or oxide or (refractive index)) same (multilayer or (multi layer) or (multiple layer) or ((3 or three or 4 or four or five or 5 or 6 or six or seven or 7 or eight or 8 or nine or 9) layer)))	738	L7
USPT,PGPB	(sputter\$3 with (rate near3 deposit\$3) with (depend\$4 or determin\$5) near5 temperature)	9	L6
USPT,PGPB	(sputter\$3 near5 (rate near2 deposit\$3) near5 (depend\$4) near5 temperature)	0	L5
USPT,PGPB	(sputter\$3 near5 (rate near2 deposit\$3) near5 (depend\$4) near5 temperature near5 substrate)	0	L4
USPT,PGPB	(sputter\$3 near5 (rate near2 deposit\$3) near5 (experiment\$5 or optimiz\$7 or determin\$3 or depend\$4))	65	L3
USPT,PGPB	(sputter\$3 near5 temperature near5 (experiment\$5 or optimiz\$5 or determin\$3 or depend\$4))	137	L2
USPT,PGPB	(sputtering with temperature with (rate near3 deposit\$3) with (experiment\$5 or optimiz\$5 or determin\$3 or depend\$4))	13	L1